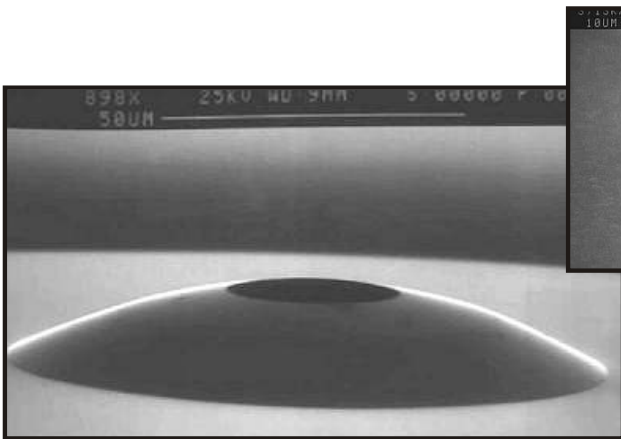
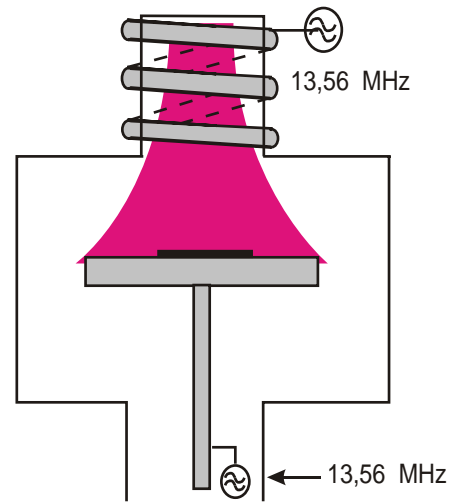


Plasmalab Data

InP - Lenses by RIE and ICP-RIE



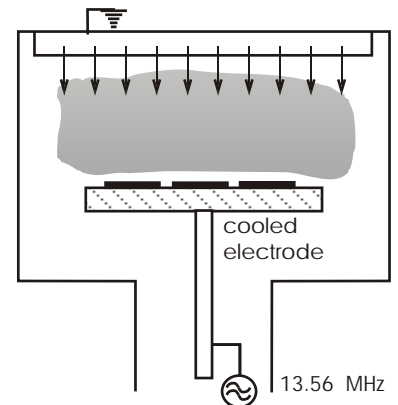
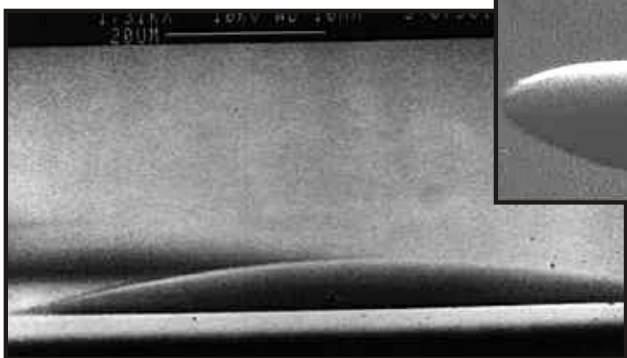
The SEM shows a lens etch stopped at 90 % of the total etch time.



Plasmalab 80 Plus

Plasmalab System 100

Plasmalab System 133



Technology:

- CI based processes
- (a) Parallel Plate Configuration RIE-Mode (13.56 MHz)
- (b) ICP - RIE with Inductive Coupled Plasma Source

Results:

- Rate (a) 50 nm/ min, (b) 150 nm/ min
- Selectivity controllable from (a) 1.5 to 2.5, (b) 0.9 - 1.1 : 1
- uniform process
- smooth surface for low signal attenuation: surface roughness < 10 nm (for ICP)

